

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Akshey Seghal

Application No.: 10/620,895

Filed: July 16, 2003

For: COMPOSITIONS AND METHOD FOR
REMOVING PHOTORESIST AND/OR
RESIST RESIDUE AT PRESSURES
RANGING FROM AMBIENT TO
SUPERCRITICAL



Confirmation No.: 8934

Group Art Unit: 1746

Examiner: Bibi Sharidan Carrillo

**RESPONSE TO OFFICE ACTION
MAILED JUNE 28, 2004**

353 Sacramento St., Suite 2200
San Francisco, CA 94111
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M/S NON-FEE AMENDMENT
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited
with the United States Postal Service as First Class Mail in an
envelope, addressed to: Commissioner for Patents, P.O.
Box 1450, Alexandria, VA 22313-1450 on Sept. 27, 2004.

STALLMAN & POLLOCK LLP

Dated: 09/27/2004 By:

Georgia K. Stith

Sir:

In response to the Office Action mailed June 28, 2004, please amend the above-identified
application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this
paper.

Remarks/Arguments begin on page 7 of this paper.